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10/24/03
(Date of Deposit)

Karen Cinq-Mars
(Signature)

10/24/03
(Date)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of : October 23, 2003
Huang et al. :
Serial No. : Examiner:
Filed: Herewith : IBM Corporation
Dept. 18G/Bldg. 300-482
2070 Route 52
Hopewell Junction,
New York 12533-6531
Title: LOW-ACTIVATION ENERGY
SILICON-CONTAINING RESIST
SYSTEM :

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

In compliance with the duty of disclosure under
37 C.F.R. § 1.56 and in accordance with the practice under
37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to
the documents listed on the enclosed Form PTO-1449. Copies of the
listed documents are also enclosed, excluding US patents.

It is respectfully requested that the above information be
considered by the Examiner and that a copy of the enclosed Form
PTO-1449 be returned indicating that such information has been
considered.

Applicants undersigned attorney may be reached by telephone

FIS920030330

at (845) 894-6919. All correspondence should continue to be directed to the below listed address.

Respectfully submitted,

 10/23/03

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TML/kcm

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>	ATTY DOCKET NO. FIS920030330US1	SERIAL NO.
	Huang et al.	
	FILING	GROUP

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	2002/0081520	06-27-02	Sooriyakumaran et al.			
	2001/0036594	11-01-01	Kozawa et al.			
	6,531,260	03-11-03	Iwasawa et al.			
	6,420,088	07-16-02	Angelopoulos et al.			
	6,623,909	09-23-03	Hatakeyama et al.			
	2003/0113658	06-19-03	Ebata et al.			
	6,043,003	03-28-00	Bucchignano et al.			
	6,037,097	03-14-00	Bucchignano et al.			
	5,712,078	01-27-98	Huang et al.			
	6,087,064	07-11-00	Lin et al.			
	2002/0090572	07-11-02	Sooriyakumaran et al.			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

	"Effects of resist components on image spreading during postexposure bake of chemically amplified resists", Hinsberg et al. Proceedings of SPIE Vol. 3999 (2000), ppgs. 148-160 "Determination of coupled acid catalysis-diffusion processes in a positive-tone chemically amplified photoresist" Houle et al. Journal Vac. Sci. Technology B 18 (4) Jul/Aug 2000, ppgs. 1874-1885
	"Direct measurement of the reaction front in chemically amplified photoresists" Lin et al. Science, Vol. 297, 19 July 2002, ppgs. 372-375 "Modeling and simulations of a positive chemically amplified photoresist or ex-ray lithography", Krasnoperova et al., Journal Vac. Sci. Technology B 12 (6) Nov/Dec 1994, ppgs. 3900-3904

EXAMINER	DATE CONSIDERED
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	5,985,524	11-16-99	Allen et al.			
	2002/0058204	05-16-02	Khojasteh et al.			
	2003/0073040	04-17-03	Iwasawa et al.			
	6,420,084	07-16-02	Angelopoulos et al.			

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	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	0 628 876 A1	05-25-94	EPO				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Appl. no. 10/241,937, FIS9-2002-0057US1 "Low silicon-outgassing resist for bilayer lithography" Kwong et al. Filed 9-11-02
	Appl. no. 10/604,082, FIS9-2003-0159US1 "Process for forming features of 50 nm or less half-pitch with chemically amplified resist imaging" Medeiros et al., Filed 06-25-03
	Appl. no. 10/026,184, FIS9-2001-0380US1 "Underlayer compositions for multilayer lithographic processes", Khojasteh et al., Filed 12-21-01
	Appl. No. 10/079,289, YOR9-2000-0693US2, "Substantially transparent aqueous base soluble polymer system for use in 157 nm resist applications" Sooriyakumaran et al., Filed 02-20-02

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